

Form PTO-1449 (Modified)	Atty Docket No. H1788	Serial No. 10/677,154
<b>LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT</b> (Use several sheets if necessary)	Applicant: Capodieci	
	Filing Date 10/1/03	Group 2825 <del>Not yet assigned</del>



## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Sub-class	Filing Date if Appropriate
NL	6,243,855	6/2001	Kobayashi, et al.			
A	6,381,731	4/2002	Grodd			
	6,397,372	5/2002	Bozkus, et al.			
	6,415,421	7/2002	Anderson, et al.			
✓	6,425,113	7/2002	Anderson, et al.			
NL	6,430,737	8/2002	Cobb, et al.			

## OTHER ART

Examiner Initial	Author, Title, Date, Pertinent Pages, etc.
NL	Schellenberg, et al. A New Process Monitor for Reticles and Wafers: The MEEF Meter, Presented at SPIE's Microlithography 2000 Symposium, February 27 to March 3, 2000.
A	Schulze and Lacour. A GDS-based Mask Data Preparation Flow - Data Volume Containment by Hierarchical Data Processing. Mentor Graphics; Deep Submicron Technical Publications, November 2002.
	Torres and Maurer. Alternatives to Alternating Phase Shift Masks for 65nm. Mentor Graphics; Deep Submicron Technical Publications, November 2002.
	Torres, et al. Design Verification Flow for Model Assisted Double Dipole Decomposition. Mentor Graphics; Deep Submicron Technical Publications, September 2002.
✓	Capodieci, et al. Effects of Advanced Illumination Schemes on Design Manufacturability and Interactions with Optical Proximity Corrections. Mentor Graphics; Deep Submicron Technical Publications, September 2000.
NL	Cobb and Sahouria. Hierarchical GDSII-based fracturing and job deck system. Mentor Graphics; Deep Submicron Technical Publications, November 2001.

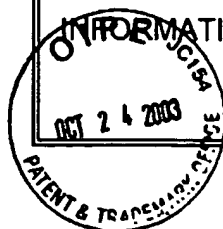
EXAMINER <i>Nam</i>	DATE CONSIDERED <i>06/27/05</i>
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

## Information Disclosure Statement PTO-1449 (Modified)

The identification of any reference is not intended to be, and should not be understood as being, an admission that such publication, in fact, constitutes "prior art" within the meaning of applicable law since, for example, a given reference may have a later effective date than first seems apparent or the reference may have an effective date which can be antedated. The "prior art" status of any reference is a matter to be resolved during prosecution.

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## OTHER ART

Examiner Initial	Author, Title, Date, Pertinent Pages, etc.
NL	Schellenberg. Impact of RET on Physical Layouts. Mentor Graphics; Deep Submicron Technical Publications, April 2001.
↑	Schellenberg, et al. OPC Beyond 0.18 $\mu\text{m}$ : OPC on PSM Gates. Mentor Graphics. Mentor Graphics; Deep Submicron Technical Publications, November 2001. Presented at SPIE's Microlithography 2000 Symposium February 27 - March 3, 2000.
	Torres, et al. RET Compliant Cell Generation for sub-130nm Processes. Mentor Graphics; Deep Submicron Technical Publications, June 2002.
	Vandenberghe, et al. (Sub-) 100nm Gate Patterning Using 248nm Alternating PSM. Mentor Graphics; Deep Submicron Technical Publications, May 2001.
↓	Granik, et al. Sub-resolution Process Windows and Yield Estimation Technique Based on Detailed Full-chip CD Simulation. Mentor Graphics; Deep Submicron Technical Publications, September, 2000.
NL	Schellenberg and Moore. Verifiable OPC Methodologies. Mentor Graphics; Deep Submicron Technical Publications, March, 1999.

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